

Amendments to the Specification:

Please replace the paragraph beginning at page 4, line 3, with the following amended paragraph:

The laser irradiation apparatus according to the present invention comprises a first laser oscillator generating a first pulsed laser beam with a wavelength of visible light or a shorter wavelength than that of visible light and a second laser oscillator generating a second CW laser beam having a wavelength of fundamental wave. The shape and the position of the beam spots of the first and second laser beam are controlled by a first and a second optical system respectively. And the beam spots of the first and second laser beam are overlapped by these two optical systems. In addition, the laser irradiation apparatus according to the present invention comprises a means to control the relative position of the beam spots of the first and the second laser beam with respect to the processing object.